

ISPlasma is specialized international symposium where about 1,000 world-leading scientists and engineers can get together in the Tokai region (central Japan) to discuss latest researches in the fields of advanced plasma science, its application for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. We aim that holding of this symposium stimulates progress of plasma science and its application, and contributes to the improvement of social life.

Related Fields

PLASMA SCIENCE

- Plasma Sources and Diagnostics
- Deposition and Modification of Thin Film
- Etching Process
- PlasmaBio and Medicine
- Plasma for Nanotechnology
- Emerging Plasma Technology

NITRIDE SEMICONDUCTORS

- Crystal Growth of GaN and Related Materials
- MBE Growth of Nitrides
- Characterization
- Device Processing
- Optical Devices
- Electrical Devices

NANOMATERIALS

- Nanocarbon Materials
- Porous Materials
- Surface Modification/Surface Functionalization
- Composite/Functionally Graded Materials
- Nanoparticles/Nanowires/Nanorods
- Nanomaterials for Energy Applications
- Soft Nano Materials

Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP).

Instruction for submitting papers will be informed by late December.

Exhibition

During the symposium, enterprises and related organizations will exhibit at the venue.

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors and Nanomaterials will be held on Sun, March 2, PM.

Focused Sessions

Power SiC/Nitride devices and Plasma collaboration Industry-Academia Collaboration

Registration

Please register on our website.

Advanced Online Registration is required.

Registration Fee :	General	Student
Early Registration (Before Jan 31, 2014)	JPY 40,000	JPY 10,000
Late Registration (Until Feb 20, 2014)	JPY 45,000	JPY 14,000
On-site Registration	JPY 50,000	JPY 18,000
Tutorial Fee :		
Participant in Main Symposium	JPY 5,000	JPY 2,000
Tutorial Registration Only	JPY 10,000	JPY 5,000
Banquet Fee (on March 4, 2014)	JPY 5,000	JPY 2,000

* Refunds cannot be made at any reason.

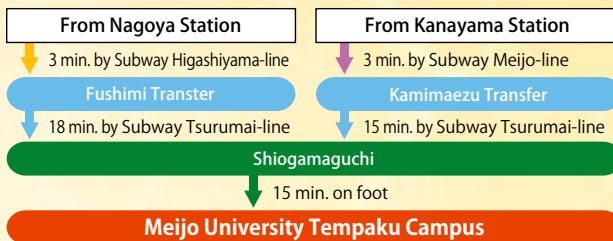
Those attending only the Industry-Academia Collab. Session on March 4, PM.

Schedule at a glance

Mar. 2 (Sun)	Tutorial Sessin Welcome Party at Meijo University
Mar. 3 (Mon)	Opening Plenary Lecture: Makoto Konagai (Tokyo Institute of Technology) Technical Session Poster Session
Mar. 4 (Tue)	Technical Session Poster Session Panel Discussion "How We Fire up the Innovation Engine? (II) - Towards the Establishment of Global Innovation Cluster -" Banquet at Meijo Shokudo, Meijo University
Mar. 5 (Wed)	Technical Session Poster Session Panel Discussion "Prospects of Solid State Lighting"
Mar. 6 (Thu)	Technical Session Poster Session Panel Discussion "Solution of energy problem using current generation Si, SiC and GaN based power devices" Award Closing

Venue

Meijo University | 1-501, Shiogamaguchi, Tempaku-ku, Nagoya JAPAN
Phone : +81-52-832-1151 (Representation)



6th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials /
7th International Conference on Plasma-Nano Technology & Science

ISPlasma2014/IC-PLANTS2014

March 2-6, 2014

Meijo University, Nagoya, Japan

Organizing Committee

Chairperson

Hirotaka Toyoda, Plasma Nanotechnology Research Center, Nagoya University

Vice-Chairperson

Nagahiro Saito, Nagoya University

Keiji Nakamura, Chubu University

Akihiro Wakahara, Toyohashi University of Technology

Sponsored by : The Japan Society of Applied Physics
ISPlasma2014 / IC-PLANTS2014 Organizing Committee

Co-sponsored by : Nagoya University, Nagoya Institute of Technology, Meijo University,
Chubu University, The Japan Society of Plasma Science and Nuclear
Fusion Research, The Japanese Association for Crystal Growth

Contact

Secretariat : Inter Group Corp

E-mail : isplasma@intergroup.co.jp Website : <http://www.isplasma.jp/>

<http://www.isplasma.jp/>



MAR
4
SUN

TUTORIAL SPEAKERS

PLASMA SCIENCE

U. Czarnetzki (Ruhr-Universität Bochum, GERMANY)
M. Nagatsu (Shizuoka University, JAPAN)

NITRIDE SEMICONDUCTORS

S. Kamiyama (Meijo University, JAPAN)
W. Walukiewicz (Solar Energy Materials Research Group, USA)

NANOMATERIALS

A. Toriumi (The University of Tokyo, JAPAN)

MAR
5
MON

PLENARY SPEAKER

Makoto Konagai (Tokyo Institute of Technology, JAPAN)

KEYNOTE SPEAKERS

PLASMA SCIENCE

W. G. (Bill) Graham (Queen's University Belfast, UK)

NITRIDE SEMICONDUCTORS

H. Ohashi (AIST, JAPAN)

NANOMATERIALS

Y. Okada (The University of Tokyo, JAPAN)

PLASMA BIO & MEDICINE

Focused Session

M. Hori (Nagoya University, JAPAN)

SOLID STATE LIGHTING

H. Fujioka (The University of Tokyo, JAPAN)

POWER DEVICE

N. Otsuka (Panasonic Corporation, JAPAN)

INDUSTRY-ACADEMIA COLLABOTATION

M. Frey (Embassy of Swizerland, JAPAN)
S. Fujimura (Tokyo Institute of Technology, JAPAN)
E. Yamaguchi (Doshisha University, JAPAN)
T.B.A

INVITED SPEAKERS

PLASMA SCIENCE

W. Choe (KAIST, KOREA)
M. Izawa (Hitachi Hi-Technologies Corporation, JAPAN)
X. Pi (Zhejiang University, CHINA)
J. Roepcke (Leibniz Institute for Plasma Science and Technology (INP Greifswald), GERMANY)
K. Sasaki (Hokkaido University, JAPAN)
R. Scaffaro (Palermo University, ITALY)
H. Takao (Kagawa University, JAPAN)
J.S. Wu (National Chiao Tung University, TAIWAN)

NITRIDE SEMICONDUCTORS

Y. Cordier (CNRS – CRHEA, FRANCE)
H. Fukuyama (Tohoku University, JAPAN)
F. Fukuyo (Hamamatsu Photonics K.K., JAPAN)
S. Ishizawa (Sophia University, JAPAN)
T.C. Lu (National Chiao Tung University, TAIWAN)
M. Onomura (TOSHIBA America Electronic Components, Inc., USA)

NANOMATERIALS

J.G. Duh (National Tsing Hua University, TAIWAN)
X. Jiang (The Chinese Academy of Sciences, CHINA)
K. Kaneko (Shinshu University, JAPAN)
D.G. Kim (Korea Institute of Materials Science, KOREA)
Y. Kumai (Toyota Central R&D Labs., INC., JAPAN)
M. Sankaran (Case Western Reserve University, USA)
T. Setoyama (Mitsubishi Chemical Corporation, JAPAN)
M. Terrones (Shinshu University, JAPAN)

PLASMA BIO & MEDICINE

Focused Session

J. H. Shin (KAIST, JAPAN)

SOLID STATE LIGHTING

K. Itatani (Sophia University, JAPAN)
J.I.Shim (Hanyang University, KOREA)
J.Y. Tsao (Sandia National Laboratories, USA)
C.Weisbuch (University of California / Ecole Polytechnique, USA / FRANCE)

POWER DEVICE

I.C. Kizilyalli (Avogy Inc., USA)
Y. Otogi (Hitachi Metals, Ltd., JAPAN)

PANEL DISCUSSION

March 4 **TUE**

How We Fire up the Innovation Engine?(II) **Focused Session**
- Towards the Establishment of Global Innovation Cluster -

<Moderator> E. Yamaguchi (Doshisha University, JAPAN)
<Panelist>
M. Frey (Embassy of Swizerland, JAPAN)
S. Fujimura (Tokyo Institute of Technology, JAPAN)
H. Tsukamoto (CONNEXX SYSTEMS Corporation, JAPAN)
T.B.A

March 5 **WED**

Prospects of Solid State Lighting **Focused Session**

<Moderator> S. Kamiyama (Meijo University, JAPAN)
<Panelist>
H. Fujioka (The University of Tokyo, JAPAN)
K. Itatani (Sophia University, JAPAN)
T.C. Lu (National Chiao Tung University, TAIWAN)
M. Onomura (TOSHIBA America Electronic Components, Inc., USA)
J.I.Shim (Hanyang University, KOREA)
J.Y. Tsao (Sandia National Laboratories, USA)
C.Weisbuch (University of California / Ecole Polytechnique, USA / FRANCE)

March 6 **THU**

Solution of energy problem using current generation Si, SiC and GaN based power devices **Focused Session**

<Moderator> M. Kuzuhara (University of Fukui, JAPAN)
<Panelist>
I.C. Kizilyalli (Avogy Inc., USA)
T. Nakamura (ROHM Co., Ltd., USA)
Y. Otogi (Hitachi Metals, Ltd., JAPAN)
N. Otsuka (Panasonic Corporation, JAPAN)

* For detailed program, please visit our website.

* Program and speakers listed above may change.
* Listed in alphabetical order.